

REMARKS

This Amendment is being filed in response to the Final Office Action mailed June 17, 2011, which has been reviewed and carefully considered. By means of the present amendment, independent the claims have been amended for better clarity. Accordingly, no new issues requiring a new search have been introduced and entry of the present amendment is respectfully requested. Reconsideration and allowance of the present application in view of the amendments made above and the remarks to follow are respectfully requested.

Claims 1-19 are pending in the Application, where claims 1 and 7 are independent.

In the Final Office Action, claims 1-19 are rejected under 35 U.S.C. §102(b) over U.S. Patent No. 6,232,613 (Silfvast). This rejection is respectfully traversed. It is respectfully submitted that the claims are patentable over Silfvast for at least the following reasons.

Silfvast is directed to an "angular pumped and emitting capillary (APEC) discharge light source having a blocking electrode." (Abstract, lines 1-2) "The blocking electrode prevents debris generated within the capillary from being expelled onto collecting optics," shown in FIG 1 as reference numeral 50, that collect radiation E, E1, E2 emitted from the Silfvast source. (Silfvast, Abstract, lines 6-8; see also column 4, lines 52-60) That is, a debris trap, such as a blocking electrode 130 shown in FIG 2 or metal electrode 310 shown

in FIG 4B, "provides a direct blocking path for any debris." (Silfvast, column 5, lines 52-53)  
As shown in FIGs 4A-4B, "[g]as G is flowed into the discharge region through the axial bore hole 315 in the metal electrode 310 located at the end of the capillary from which the useful radiation is emitted. Gas is admitted to this electrode by a gas inlet 311." (Silfvast, column 6, lines 37-41) In Silfvast, the **SAME gas** flows through the Silfvast source, which may be "Xenon helium, neon, argon, and krypton." (Silfvast, column 6, line 32)

It is respectfully submitted that Silfvast does not disclose or suggest the present invention as recited in independent claim 1, and similarly recited in independent claim 7 which, amongst other patentable elements, recites (illustrative emphasis provided):


guiding a first gas at a first side of a particle trap arranged in a wall of a chamber between the radiation source and the particle trap; introducing a second gas into the chamber at a second side of the particle trap, wherein the first side is different from the second side; and adjusting a pressure of the second gas to be at least as high as a pressure of the first gas, wherein the **second gas is different from the first gas and the second side does not include the first gas.**

Silfvast does not disclose or suggest having two different gases that flow in different parts of the Silfvast source. Rather, the **same** gas flows throughout the Silfvast source. Accordingly, it is respectfully requested that independent claims 1 and 7 be allowed. In addition, it is respectfully requested that claims 2-6 and 8-19 also be allowed at least based on their dependence from independent claims 1 and 7 as well as their individually patentable elements.

In addition, Applicants deny any statement, position or averment of the Examiner that is not specifically addressed by the foregoing argument and response. Any rejections and/or points of argument not addressed would appear to be moot in view of the presented remarks. However, the Applicants reserve the right to submit further arguments in support of the above stated position, should that become necessary. No arguments are waived and none of the Examiner's statements are conceded.

In view of the above, it is respectfully submitted that the present application is in condition for allowance, and a Notice of Allowance is earnestly solicited.

Respectfully submitted,

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